

# Abstracts

## **High gain, high efficiency, low voltage, medium power Si-bipolar transistor suitable for integration**

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*F. van Rijs, R. Dekker, P.H.C. Magnee, R. Vanoppen, E. v.d. Heijden, B.N. Balm and L.C. Colussi. "High gain, high efficiency, low voltage, medium power Si-bipolar transistor suitable for integration." 1997 Radio Frequency Integrated Circuits (RFIC) Symposium 97. (1997 [RFIC]): 15-18.*

Medium power transistors in a high performance double polysilicon bipolar process have been fabricated. On-wafer loadpull measurements show high gain (15 dB) and high maximum efficiency (60%) at 1.8 GHz with 27 dBm of output power. These results were obtained with a low supply voltage of 3.5 V. More importantly, these results were obtained with transistors with a buried layer having a collector contact at the top, which makes it possible to integrate power amplifiers on chip.

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